

# SEARCH REQUEST FORM

Scientific and Technical Information Center

Requester's Full Name: Sim J. Lee Examiner #: 7660 Date: 12-28-05  
Art Unit: 1752 Phone Number 301 2133 Serial Number: 101248778  
Mail Box and Bldg/Room Location: 9060 Results Format Preferred (circle): PAPER DISK E-MAIL

If more than one search is submitted, please prioritize searches in order of need.

Please provide a detailed statement of the search topic, and describe as specifically as possible the subject matter to be searched. Include the elected species or structures, keywords, synonyms, acronyms, and registry numbers, and combine with the concept or utility of the invention. Define any terms that may have a special meaning. Give examples or relevant citations, authors, etc, if known. Please attach a copy of the cover sheet, pertinent claims, and abstract.

Title of Invention: Hz. See D.O

Inventors: (please provide full names):

**Earliest Priority Filing Date:**

*\*For Sequence Searches Only\** Please include all pertinent information (parent, child, divisional, or issued patent numbers) along with the appropriate serial number.

P12. Search for a polymer that is made from the following monomer. (1B)

or C1C) of C1. #2

in each of the formula (1b) and (1c).

$$R_1 = -Z \text{ or } -Y-Z$$

CY = linear / branched alkylene or  
monocyclic / polycyclic alkylene)

Z = substituted diamantane, triamantane  
or mixtures thereof

(All attached page for the structures for diamantane and triamantane)

**STAFF USE ONLY**

Searcher:                     

Searcher Phone #: \_\_\_\_\_

Searcher Location: \_\_\_\_\_

Date Searcher Picked Up:

Date Completed: 1-4-06

Searcher Prep &amp; Review Time: \_\_\_\_\_

Clerical Prep Time: \_\_\_\_\_

Online Time: \_\_\_\_\_

### Type of Search

<sup>1</sup>NA Sequence (#) . . . . .

AA Sequence (#)

Structure (#)

### Bibliographic

## Litigation

Fulltext

### • Patent Family

Other

**Vendors and cost where applicable**

STN

### Dialog

Questel/Orbit

Dr. Link

Lexis/Nexis.

### Sequence Systems

WWW/Internet

Other (specify) \_\_\_\_\_

=> file reg

FILE 'REGISTRY' ENTERED AT 17:42:00 ON 04 JAN 2006  
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.  
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=> d his

FILE 'LREGISTRY' ENTERED AT 17:23:31 ON 04 JAN 2006  
E DIAMANTANE/CN

FILE 'REGISTRY' ENTERED AT 17:23:59 ON 04 JAN 2006  
E DIAMANTANE/CN

L1 1 S E3  
E TRIAMANTANE/CN  
L2 1 S E3

FILE 'LREGISTRY' ENTERED AT 17:24:39 ON 04 JAN 2006  
L3 STR 2292-79-7

FILE 'REGISTRY' ENTERED AT 17:31:28 ON 04 JAN 2006  
L4 0 S L3  
E 2395.1.1/RID  
L5 713 S E3  
E 4790.1.1/RID  
L6 58 S E3  
L7 248 S L5 AND PMS/CI  
L8 0 S L3 FUL

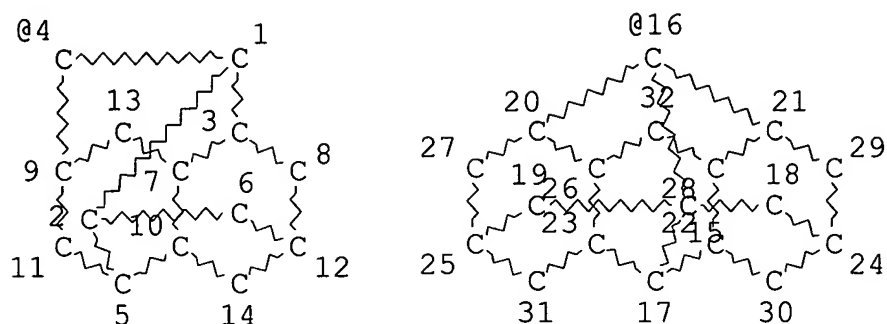
FILE 'HCAPLUS' ENTERED AT 17:38:12 ON 04 JAN 2006  
L9 243 S DAMMEL R?/AU  
L10 11751 S PHOTORESIST?/TI  
L11 64 S L9 AND L10  
SEL L11 1-64 RN

FILE 'REGISTRY' ENTERED AT 17:38:46 ON 04 JAN 2006  
L12 276 S E1-E276  
L13 3 S L12 AND (L5 OR L6)

FILE 'HCA' ENTERED AT 17:40:11 ON 04 JAN 2006  
L14 1 S L13

FILE 'REGISTRY' ENTERED AT 17:42:00 ON 04 JAN 2006

=> d 18 que stat  
L3 STR



C=C~G1  
33 34 35

SO2~G2  
@38 39

G3 42

VAR G1=O/38  
VAR G2=N/O  
VAR G3=4/16  
NODE ATTRIBUTES:-  
DEFAULT MLEVEL IS ATOM  
DEFAULT ECLEVEL IS LIMITED

GRAPH ATTRIBUTES:  
RING(S) ARE ISOLATED OR EMBEDDED  
NUMBER OF NODES IS 38

STEREO ATTRIBUTES: NONE  
L8 0 SEA FILE=REGISTRY SSS FUL L3

100.0% PROCESSED 66649 ITERATIONS  
SEARCH TIME: 00.00.01

0 ANSWERS

=> file hca  
FILE 'HCA' ENTERED AT 17:42:13 ON 04 JAN 2006  
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=> d 114 1 all hitstr

L14 ANSWER 1 OF 1 HCA COPYRIGHT 2006 ACS on STN

(author's citation)

AN 143:123042 HCA  
 ED Entered STN: 04 Aug 2005  
 TI Photoresist composition  
 IN Dammel, Ralph R.  
 PA USA  
 SO U.S. Pat. Appl. Publ., 23 pp.  
 CODEN: USXXCO  
 DT Patent  
 LA English  
 IC ICM G03C001-76  
 INCL 430270100  
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and  
 Other Reprographic Processes)  
 Section cross-reference(s): 35, 38

FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2005147915	A1	20050707	US 2003-748778	20031229
WO 2005066714	A2	20050721	WO 2004-IB4384	20041208

W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, UZ, VC, VN, YU, ZA, ZM, ZW

RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG

PRAI US 2003-748778 A 20031229

CLASS

PATENT NO.	CLASS	PATENT FAMILY CLASSIFICATION CODES
US 2005147915	ICM	G03C001-76
	INCL	430270100
	IPCI	G03C0001-76 [ICM,7]
	NCL	430/270.100
	ECLA	G03F007/039C1S
WO 2005066714	IPCI	G03F0007-00 [ICM,7]
	ECLA	G03F007/039C1S

AB The present invention relates to a photosensitive compn. useful at

wavelengths between 300 nm and 10 nm which comprises a polymer contg. a substituted or unsubstituted higher adamantane.

ST photoresist compn higher adamantane

IT Photoresists

(photoresist compn. contg. substituted or unsubstituted higher adamantane)

IT 24937-72-2P, Maleic anhydride homopolymer 177080-67-0DP, 2-Methyl-2-adamantyl methacrylate, polymer with hydroxydiamantane methacrylate and butyrolactone methacrylate 195000-66-9DP, polymer with hydroxydiamantane methacrylate and Me adamantane methacrylate and/or Me diamantane methacrylate **857284-47-0DP**, polymer with butyrolactone methacrylate and hydroxydiamantane methacrylate derivs. **857284-49-2P 857284-60-7P**

(photoresist compn. contg. substituted or unsubstituted higher adamantane)

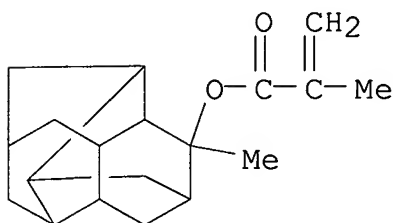
IT **857284-47-0DP**, polymer with butyrolactone methacrylate and hydroxydiamantane methacrylate derivs. **857284-49-2P**

**857284-60-7P**

(photoresist compn. contg. substituted or unsubstituted higher adamantane)

RN 857284-47-0 HCA

CN 2-Propenoic acid, 2-methyl-, decahydro-2-methyl-3,5,1,7-[1,2,3,4]butanetetraylnaphthalen-2-yl ester (9CI) (CA INDEX NAME)



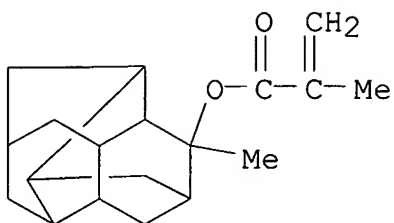
RN 857284-49-2 HCA

CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethylethyl ester, polymer with decahydro-2-methyl-3,5,1,7-[1,2,3,4]butanetetraylnaphthalen-2-yl 2-methyl-2-propenoate, 2,5-furandione and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 857284-47-0

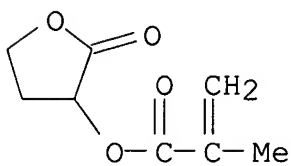
CMF C19 H26 O2



CM 2

CRN 195000-66-9

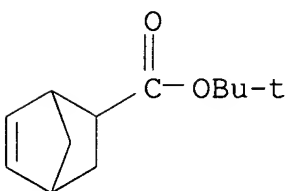
CMF C8 H10 O4



CM 3

CRN 154970-45-3

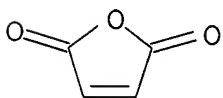
CMF C12 H18 O2



CM 4

CRN 108-31-6

CMF C4 H2 O3

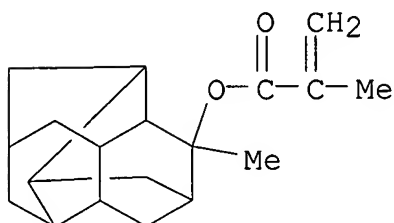


RN 857284-60-7 HCA  
CN 2-Propenoic acid, 2-methyl-, decahydro-2-methyl-3,5,1,7-[1,2,3,4]butanetetraylnaphthalen-2-yl ester, polymer with 3-hydroxytricyclo[3.3.1.1<sup>3,7</sup>]dec-1-yl 2-methyl-2-propenoate and tetrahydro-2-oxo-3-furanyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 857284-47-0

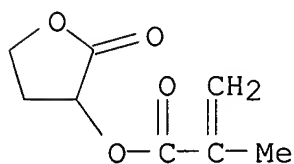
CMF C19 H26 O2



CM 2

CRN 195000-66-9

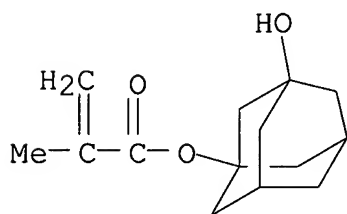
CMF C8 H10 O4



CM 3

CRN 115372-36-6

CMF C14 H20 O3



LEE 10/748,778

Page 7